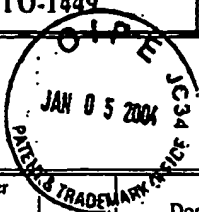


<b>INFORMATION DISCLOSURE CITATION PTO-1449</b>	Atty. Docket No. 032061	Serial No. 10/695,642
	Applicant(s): Naoya SASHIDA et al.	
	Filing Date: October 29, 2003	Group Art Unit: TBD



### U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)

### FOREIGN PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Country	Translation (Yes or No)
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